

Amendments to the Specification:

Please replace paragraph [0016] with the following amended paragraph:

[0016] Such a magnetron cathode technology has following problems in a current sputtering process requiring a small line width (0.14 ~~[[μ m]]~~ μ m or less) and high aspect ratio (5:1 or more): deposition occurs asymmetrically, film uniformity is poor, and target erosion occurs locally, thereby decreasing the efficiency of materials used.